

10/562257

Attorney's Docket No.: 17979-034US1 / 04157PUS

IAP20 Rec'd PCT/PTO 21 DEC 2005

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant : Shafer et al. Art Unit : Unknown
Serial No. : Examiner : Unknown
Filed : December 21, 2005
Title : OBJECTIVES AS A MICROLITHOGRAPHY PROJECTION OBJECTIVE
WITH AT LEAST ONE LIQUID LENS

Commissioner for Patents
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INFORMATION DISCLOSURE STATEMENT

Applicants request consideration of the references listed on the attached PTO-1449 form. Under 37 C.F.R. § 1.98 (a)(2)(ii), only copies of foreign patent documents and/or non-patent literature are enclosed. Copies of any listed U.S. patents or U.S. patent application publications can be provided upon request. A copy of a communication from a foreign patent office in a counterpart application is also enclosed.

This statement is being filed with the application. Please apply any charges or credits to Deposit Account No. 06-1050.

Respectfully submitted,

Date: 12/21/05


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| Substitute Form PTO-1449 (Modified) | U.S. Department of Commerce Patent and Trademark Office | Attorney's Docket No. 17979-034US1 | Application No. 10/562257 |
| Information Disclosure Statement by Applicant (Use several sheets if necessary) (37 CFR §1.98(b)) | | Applicant Shafer et al. | |
| | | Filing Date Herewith | Group Art Unit |

| U.S. Patent Documents | | | | | | | |
|-----------------------|-----------|-----------------|------------------|-------------------------------|-------|----------|----------------------------|
| Examiner Initial | Desig. ID | Document Number | Publication Date | Patentee | Class | Subclass | Filing Date If Appropriate |
| | AA | US2003/174408 | 9/18/2003 | Rostalski Hans-Juergen et al. | | | |
| | AB | US2005/024609 | 2/3/2005 | De Smit et al. | | | |
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| Foreign Patent Documents or Published Foreign Patent Applications | | | | | | | | |
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| Examiner Initial | Desig. ID | Document Number | Publication Date | Country or Patent Office | Class | Subclass | Translation | |
| | | | | | | | Yes | No |
| | AF | WO2005/006026 | 1/20/2005 | WIPO | | | | |
| | AG | WO2005/081067 | 9/1/2005 | WIPO | | | | |
| | AH | EP0291596B1 | 1/19/1994 | EPO | | | | |
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| Other Documents (include Author, Title, Date, and Place of Publication) | | |
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| | AM | Hoffnagle, J.A. et al. "Liquid immersion deep-ultraviolet interferometric lithography", Journal of Vacuum Science & Technology B: Microelectronics Processing and Phenomena, American Vacuum Society, New York, NY, US, vol. 17, no. 6, November 1999 (1999-11), pages 3306-3309 |
| | AN | Smith, et al. "Water-based 193nm immersion lithography", online, 28 January 2004, retrieved from the internet: URL:http://www.sematech.org/resources/litho/meetings/immersion/20040128/presentations/06%20RIT%20microstepper%20efforts_Smith.pdf , retrieved on 2005-05-24 |
| | AO | |
| | AP | |

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| Examiner Signature | Date Considered |
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